

SEMICONDUCTOR FABRICATING APPARATUS

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ABSTRACT OF THE DISCLOSURE

A resonant frequency sensor is disposed in a plasma-processing chamber included in a semiconductor
10 fabricating apparatus. A change in the resonant frequency caused by etching, sputtering or deposition is sensed in order to detect the timing of performing the maintenance of the processing chamber. If data representing the relationship between an amount of
15 etching or deposition occurring at a predetermined position in the processing chamber and occurrence of an abnormality is produced in advance, an optimal maintenance timing can be determined.